Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently amended) A process for cleaning a reactor wherein the reactor is used to coat TiO₂ onto an article, said process comprising:

providing the reactor to be cleaned wherein the reactor contains a chamber comprising a surface at least partially coated with a substance comprising TiO₂; adding to the reactor a reactive gas comprising at least one cleaning agent gas;

reacting the substance with the reactive gas to form at least one volatile product; and removing from the reactor the at least one volatile product to clean the reactor.

- 2. (Currently amended) The process of claim 1, wherein the at least one cleaning gas is selected from the group consisting of a fluorine-containing cleaning gas, a chlorine-containing cleaning gas, and combinations thereof.
- 3. (Original) The process of claim 2, wherein the at least one cleaning gas is a chlorine-containing cleaning gas.
- 4. (Original) The process of claim 3 wherein the chlorine-containing cleaning gas is at least one member selected from the group consisting of BCl_3 , $COCl_2$, HCl, Cl_2 , CIF_3 , and NF_zCl_{3-z} , where z is an integer from 0 to 2.
- 5. (Original) The process of claim 2 wherein the at least one cleaning gas is a fluorine-containing cleaning gas.

- 6. (Currently amended) The process of claim 5 wherein the fluorine-containing cleaning gas comprises at least one member selected from the group consisting of NF₃; CIF₃; CIF; SF₆; a perfluorocarbon; a hydrofluorocarbon; an oxyfluorocarbon; a hypofluorite, a fluoroperoxide; a fluorotrioxide; COF₂; NOF; F₂; NF_nCl_{3-n}, where n is a number ranging from 1 to 2; and combinations thereof.
- 7. (Original) The process of claim 6, wherein the fluorine-containing cleaning gas is NF₃.
- 8. (Original) The process of claim 1, wherein the reactive gas further comprises an inert diluent gas.
- 9. (Currently amended) The process of claim 1, wherein the reacting step is conducted by an in situ plasma, a remote plasma, an in-situ thermal source, a remote thermal source, a remote catalytic source, a photon activation source, and or combinations thereof.
- 10. (Original) The process of claim 9, wherein the reacting step is conducted by an in situ plasma.
- 11. (Original) The process of claim 9 wherein the reacting step is conducted by a remote plasma.
- 12. (Currently amended) The process of claim 1, wherein the reactive gas is conveyed to the chamber from a gas cylinder, a safe delivery system, a pipeline, a point of use delivery system, a vacuum delivery system, and or combinations thereof.

- 13. (Currently amended) The process of claim ± 5 , wherein the fluorine-containing reactive gas is formed in close proximity to the reactor by a point-of-use generator.
- 14. (Currently amended) The process of claim 1 wherein the article is selected from the group consisting of a glass-containing work piece, a metal-containing work piece, a ceramic work piece, and mixtures thereof.
- 15. (Currently amended) A process for the deposition of a TiO₂ coating on a glass article, the process comprising:

placing the glass article into a reactor;

depositing the TiO₂ coating onto the glass article and a substance comprising TiO₂ onto at least one surface within the reactor using at least one metal precursor wherein the depositing step is conducted by a process selected from the group consisting of chemical vapor deposition, vacuum deposition, spray pyrolysis and combinations thereof;

adding to the reactor a reactive gas comprising at least one cleaning agent gas; reacting the substance with the reactive gas to form at least one volatile product; and removing from the reactor the at least one volatile product to clean the reactor.

- 16. (New) The process of claim 15, wherein the at least one cleaning gas is selected from the group consisting of a fluorine-containing cleaning gas, a chlorine-containing cleaning gas, and combinations thereof.
- 17. (New) The process of claim 16, wherein the at least one cleaning gas is a chlorine-containing cleaning gas.
- 18. (New) The process of claim 17 wherein the chlorine-containing cleaning gas is at least one member selected from the group consisting of BCl₃, COCl₂, HCl, Cl₂, CIF₃, and NF_zCl_{3-z}, where z is an integer from 0 to 2.

- 19. (New) The process of claim 16 wherein the at least one cleaning gas is a fluorine-containing cleaning gas.
- 20. (New) The process of claim 19 wherein the fluorine-containing cleaning gas comprises at least one member selected from the group consisting of NF₃; CIF₃; CIF; SF₆; a perfluorocarbon; a hydrofluorocarbon; an oxyfluorocarbon; a hypofluorite, a fluoroperoxide; a fluorotrioxide; COF₂; NOF; F₂; NF_nCl_{3-n}, where n is a number ranging from 1 to 2; and combinations thereof.